

Appl. No. : 10/561,802  
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## ABSTRACT

*Amendment please enter*

*Hoa Van Le*  
08/10/10 A developer composition for resists which has a high dissolution rate (high developing sensitivity). The developer composition for resists comprises an organic quaternary ammonium base as a main component and a surfactant containing an anionic surfactant represented by formula (I).

*HOA VAN LE*  
PRIMARY EXAMINER

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